

Electronic Packaging Days 2025

Hermann Oppermann

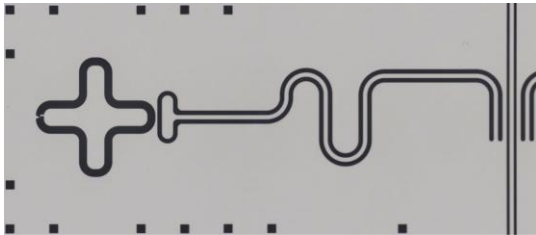
Tailoring Packaging for Advanced Quantum Applications

Packaging of advanced quantum applications

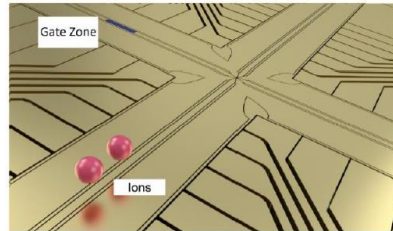
What are the challenges?

➤ A set of technologies is required to integrate fragile quantum devices into usable, scalable systems. Such as

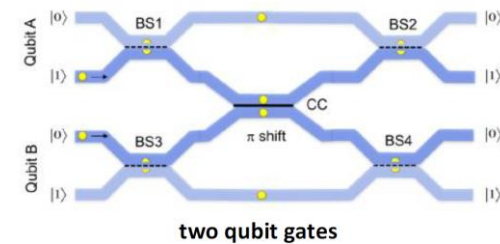
superconducting qubits



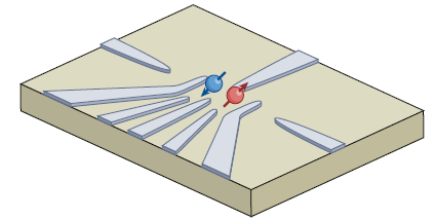
Ion traps



photonic circuits



spin-based qubits

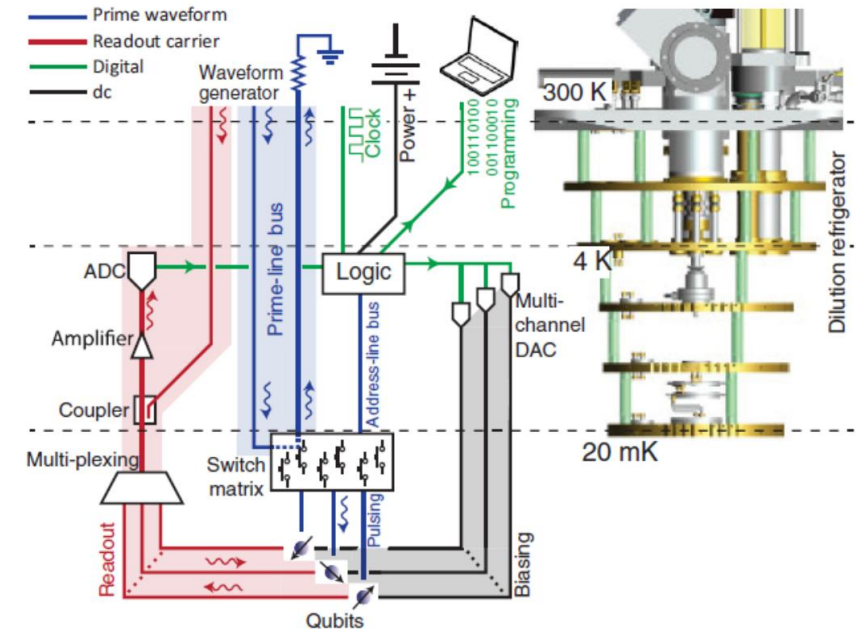


➤ Quantum packaging faces unique challenges because quantum states are extremely sensitive to

- temperature
- electromagnetic noise
- vibration
- material defects

Operating Environment and Packaging Challenges

- Temperature: 10 to 20 mK inside a dilution refrigerator.
- Scalability: quantum computer with thousands or millions of qubits
- Reliability: Bump bonds, TSVs, and superconducting interconnects must be stable at cryogenic cycles
- Integration density: Keep qubits close to each other for coupling and routing signals without crosstalk
- Wiring bottleneck: Each qubit needs multiple microwave/control lines. Higher wiring density of superconducting qubits in cryogenics
- Thermal load: Each extra coax line adds heat load, space, and noise. Thousands of coaxial lines won't fit into a dilution fridge.
- Active electronics at cryo-level must be ultra-low-power (readout circuit ~ 1 nW (30 μ A, 30 μ V).
- Cooling power is very limited: 1 W @ 4 K, but <10 μ W @ 20 mK
- Isolation: Must suppress electromagnetic interference (EMI), magnetic flux noise, and thermal photons



source: J. M. Hornibrook et al.: Cryogenic Control Architecture for Large-Scale Quantum Computing, PHYS. REV. APPLIED 3, 024010 (2015)

Core Functions of Superconducting Qubits

➤ Thermal Management

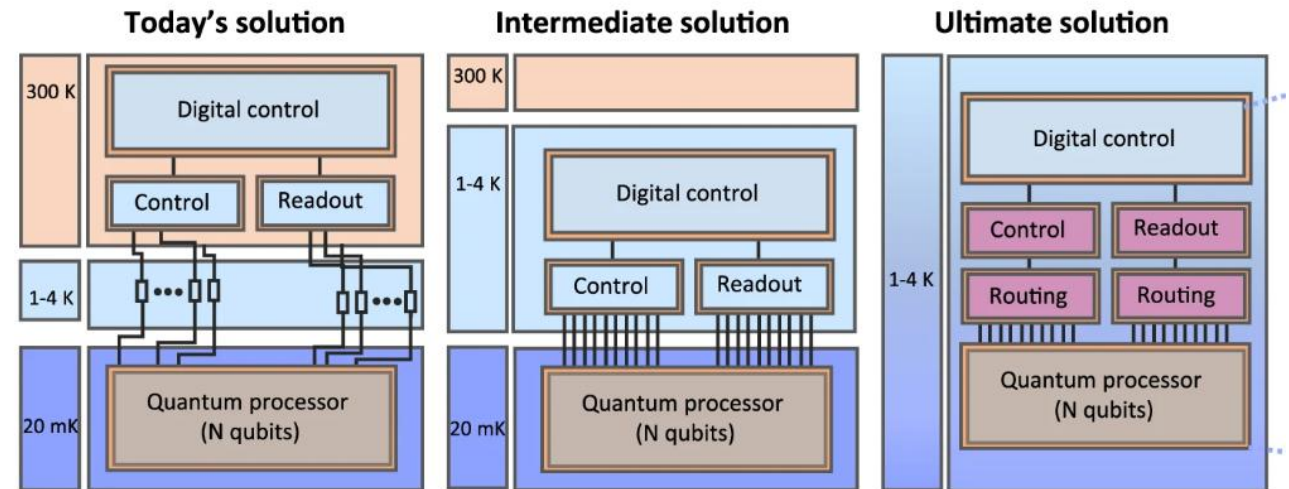
- Operation at milli-Kelvin (mK) regimes for superconducting qubits
- Minimize heat leaks between cooling stages

➤ Signal Delivery & Interconnects

- Microwave lines: low loss, low cross-talk (superconducting routing circuits)
- Wiring lines: ultra-low resistance to avoid heating in cryogenic environments

➤ Integration with Classical Control Electronics

- Cryo-CMOS or superconducting electronics: Co-packaging with qubits
→ advanced packaging
- Reduce wiring bottlenecks: moving signal processor closer to the quantum chip
→ increased I/O density

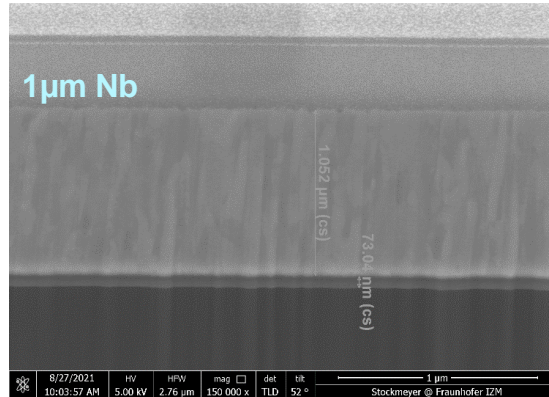


Superconducting Qubit Packaging

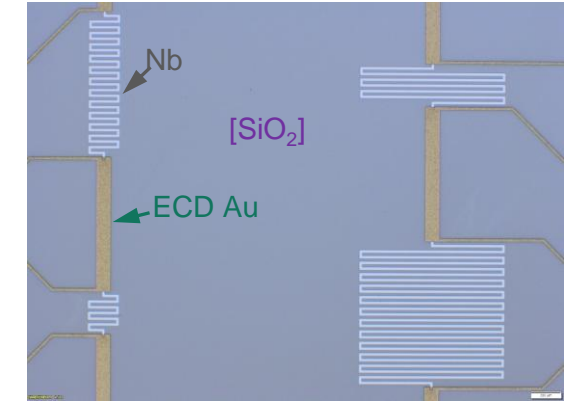
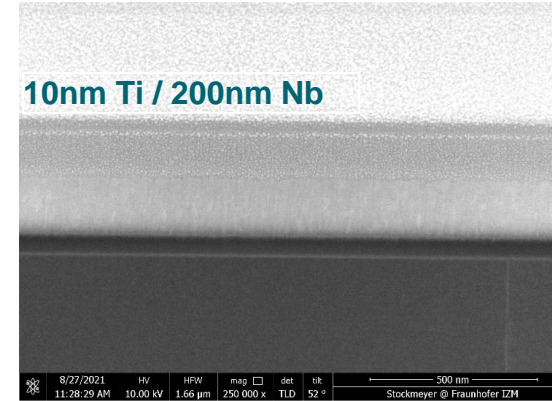
Superconductive Metallizations



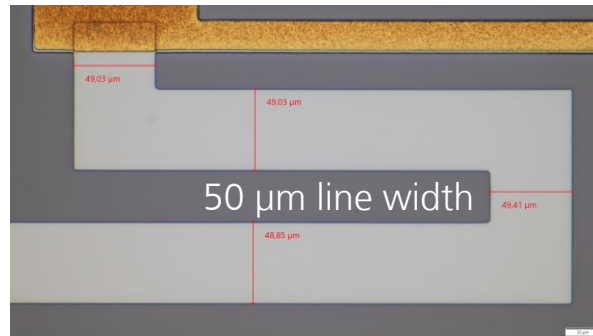
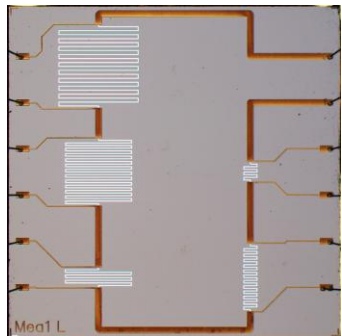
8" wafer: Nb 150nm / Au 150nm;
electroplated Au: 1.5µm



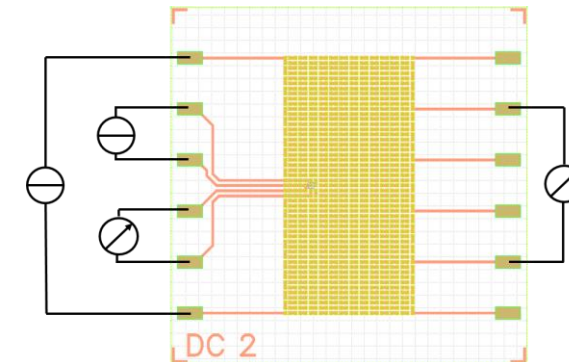
Sputter deposition of 1µm Nb, NbN, 200nm Nb and Ti / Nb



Etching of Nb; Plating of Au



Niobium patterned: 50 µm down to 5 µm line width & electroplated Au 1.5 µm



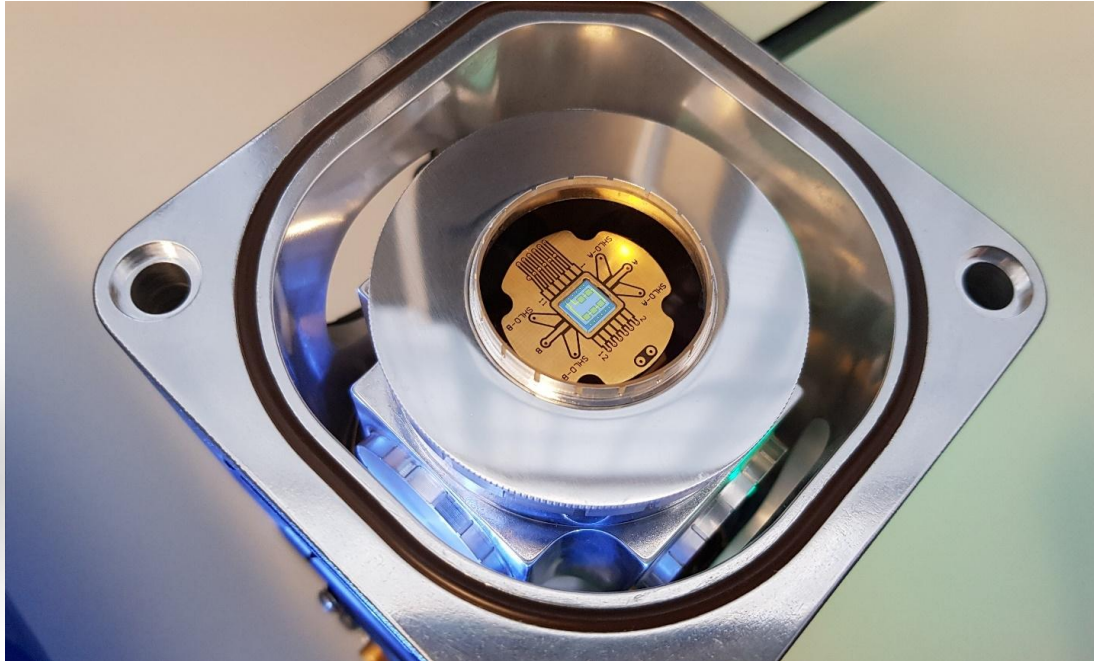
Electrical test chip:

- 5476 Bumps
- daisy-chain,
- isolation test
- 4-point-Kelvin

Flip chip test vehicle for Indium bumps on Nb

Superconducting Qubit Packaging

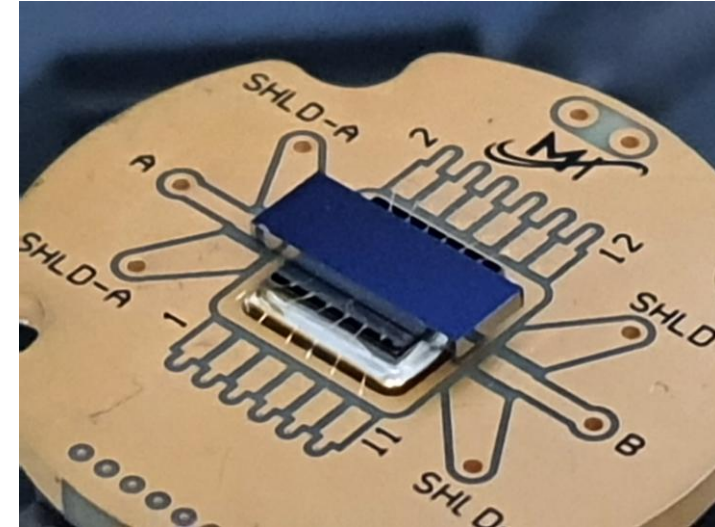
Cryogenic Testing



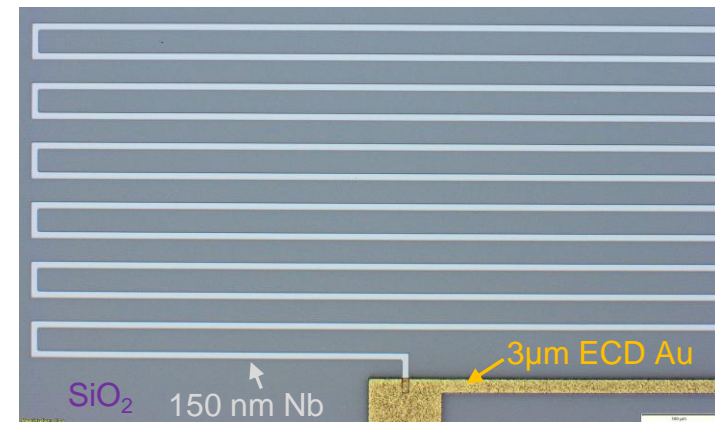
View on sample mount

Cryogenic Testing Capabilities:

- Temperature ramping between 300K and 3.2 K
- Magnetic field application up to 0.7 T
- RF capability up to 20 GHz



Flip chip bonded test vehicle with indium bumps on sample mount



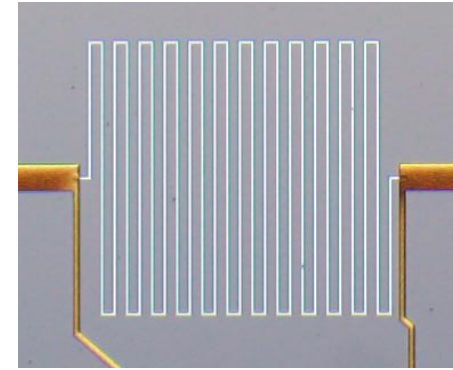
10 µm lines
50 µm pitch

Cryogenic Integration and Interconnect Technology

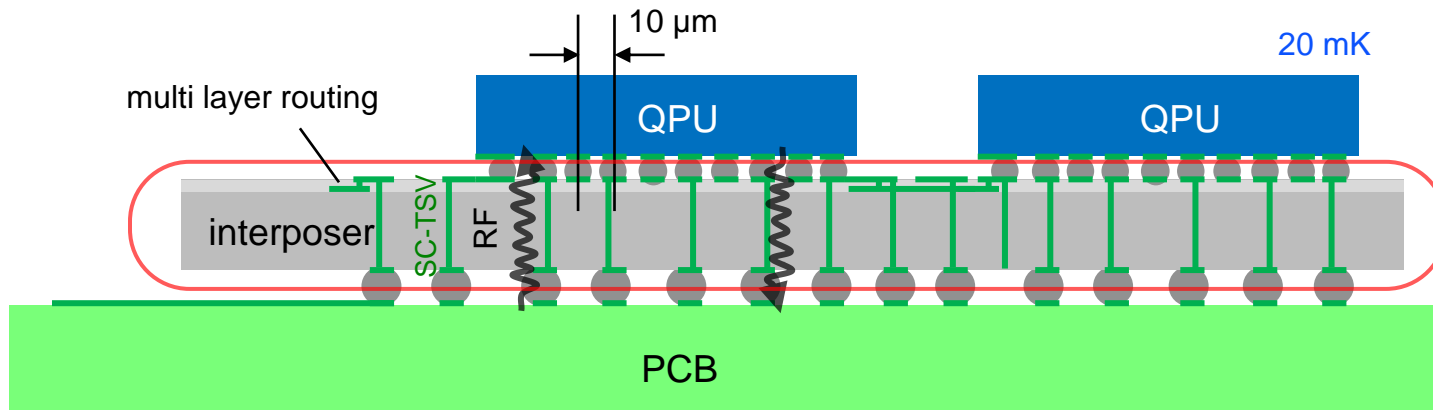
Interposer Technologie / 3D Integration

Scalability for integration of multiple QPUs

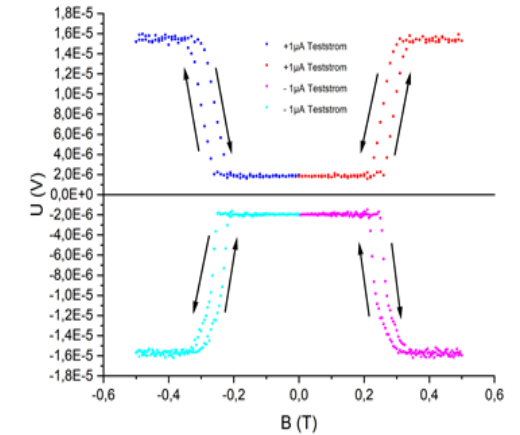
- Multilayer routing: superconductors, e.g. Nb, NbN
- Interposer with superconductive TSVs
- Low loss RF routing



Niobium 150 nm patterned



measurement of
critical magnetic
field strength



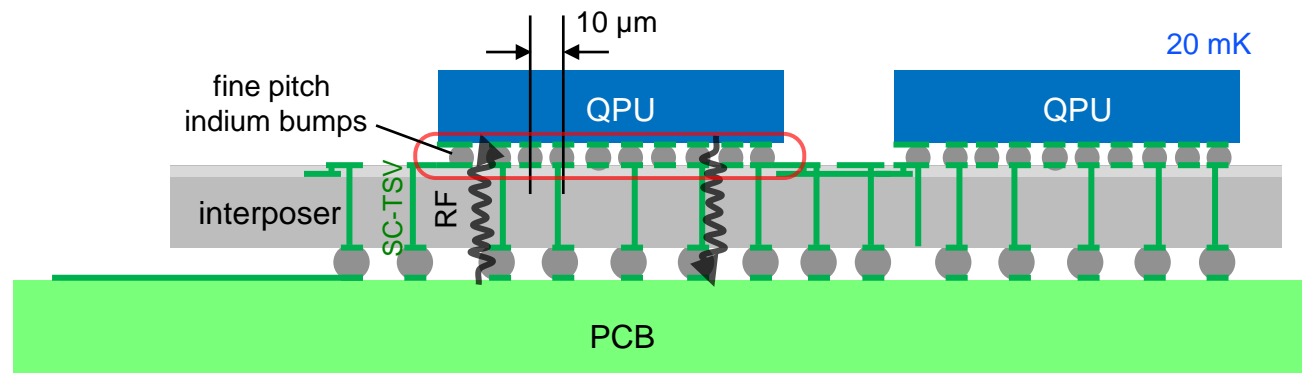
measurement of niobium
with 1μA at 3.3 K

Cryogenic Integration and Interconnect Technology

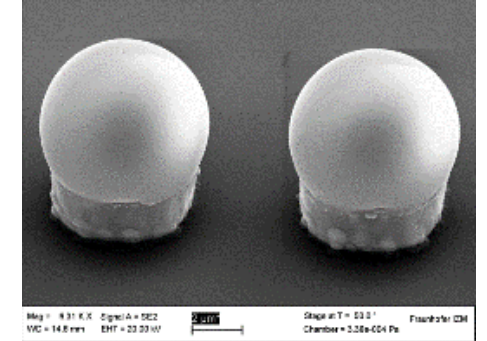
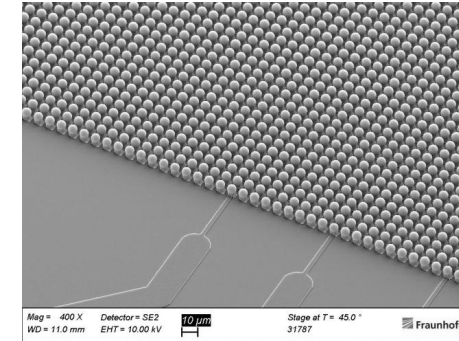
Chip Integration and Interconnect

Scalability for applications with $10^5 \dots 10^6$ qubits

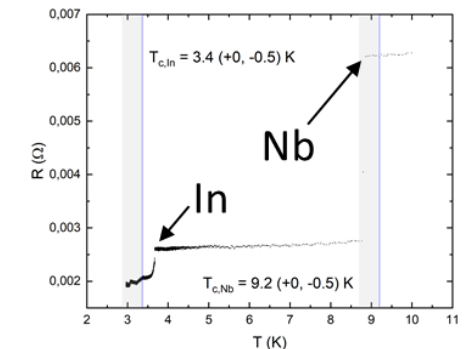
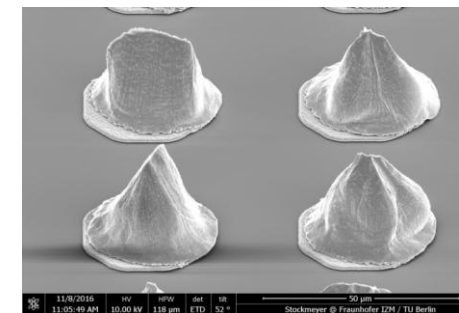
- Extreme high interconnect density for QPU
→ $< 10 \mu\text{m}$ bump pitch
- Indium & indium-tin: → superconducting bump interconnect
→ ductile at low temperatures



Low Temperature Bonding In-Au: 80°C
In-In: 30°C



electroplated indium bumps 7.5 μm pitch
4 μm bump diameter, 3.5 μm space



indium: ductile fracture mode
→ low temperature toughness

indium: critical temperature at 3.4 K

Ion Traps Qubit Packaging

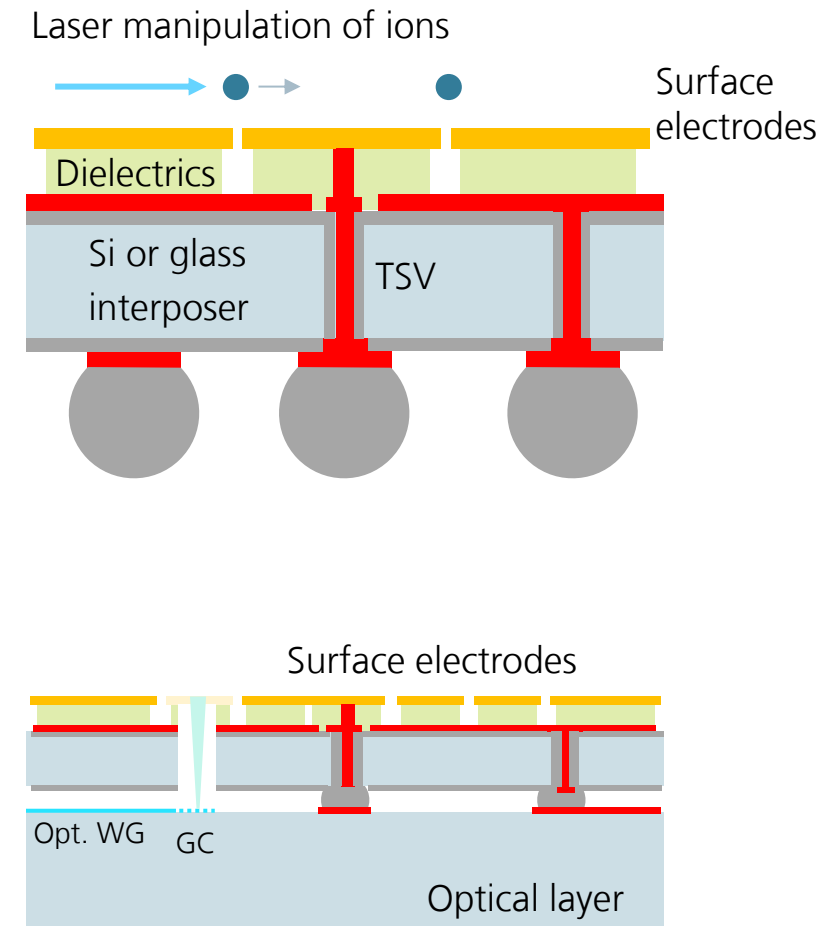
Operating Environment

Fabrication:	Semiconductor processes: Au or superconducting electrodes patterned on sapphire/Si. - mounted inside vacuum chambers using UHV-compatible packaging technologies - include chip carriers with UHV feedthroughs for electrical connections
Vacuum:	Ions are suspended in electromagnetic Paul or Penning traps. Requires UHV: $\sim 10^{-11}$ – 10^{-13} Torr. Prevents ions from collision with gas molecules.
Temperature:	Ion traps operate at room temperature, but cryogenic traps might be more stable.
Optical access:	Laser beams used for ion cooling, state preparation, and entangling operations. Each ion needs multiple laser beams; scaling to thousands is hard without photonic integration.
Electrical control:	Ions are confined by RF and DC voltages applied to electrodes on the chip. Integration with control electronics needs dense wiring without introducing noise or breaking vacuum seals.
Magnetic field control:	Qubits require stable magnetic fields.
Vibration Isolation:	Ion traps require nm-scale stability. Even slight mechanical noise can destroy precision.

Ion Traps Qubit Packaging

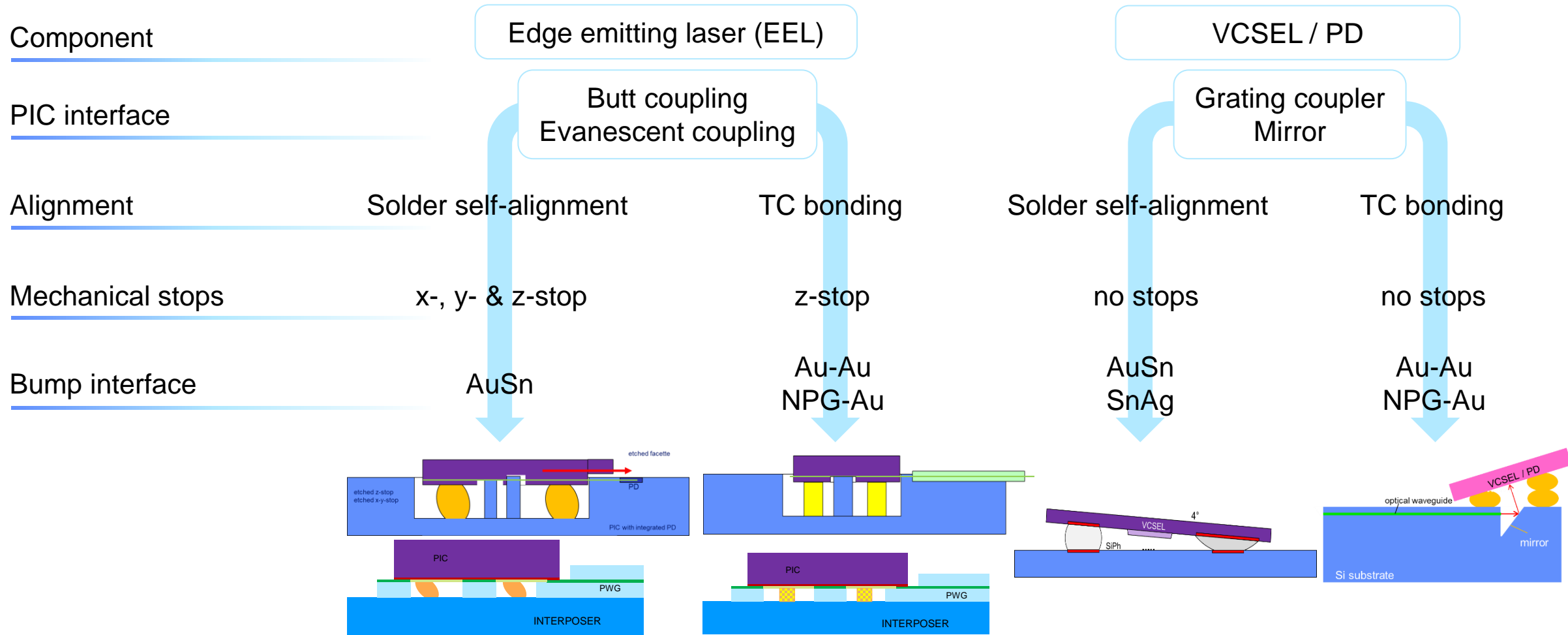
Challenges in Packaging and Possible Solutions

- **Surface-Electrode Traps:** with microfabrication electrodes are patterned flat on chips. They can be scaled for high volume, flip-chip packaged, and integrated with photonics.
 - **Integrated Photonics Packaging:** SiN waveguides route multiple laser wavelengths directly to ion positions, eliminates bulky free-space optics and dramatically improves scalability.
 - **Cryogenic Traps:** cryo temperatures improves vacuum and reduces motional heating.
 - **Compact Vacuum Modules:** sealed chip packages with integrated ion source, vacuum pumping, and optical access in a few cm³ as for modular scaling.
-
- Microfabricated surface-electrode traps with TSVs
 - Integrated photonics for scaling large number of laser beams.
 - Hermetic sealing at chip or package level to sustain UHV environment
 - Packaging should be suitable for cryogenic temperature



Quantum Packaging: Photonic Layer and Interconnect

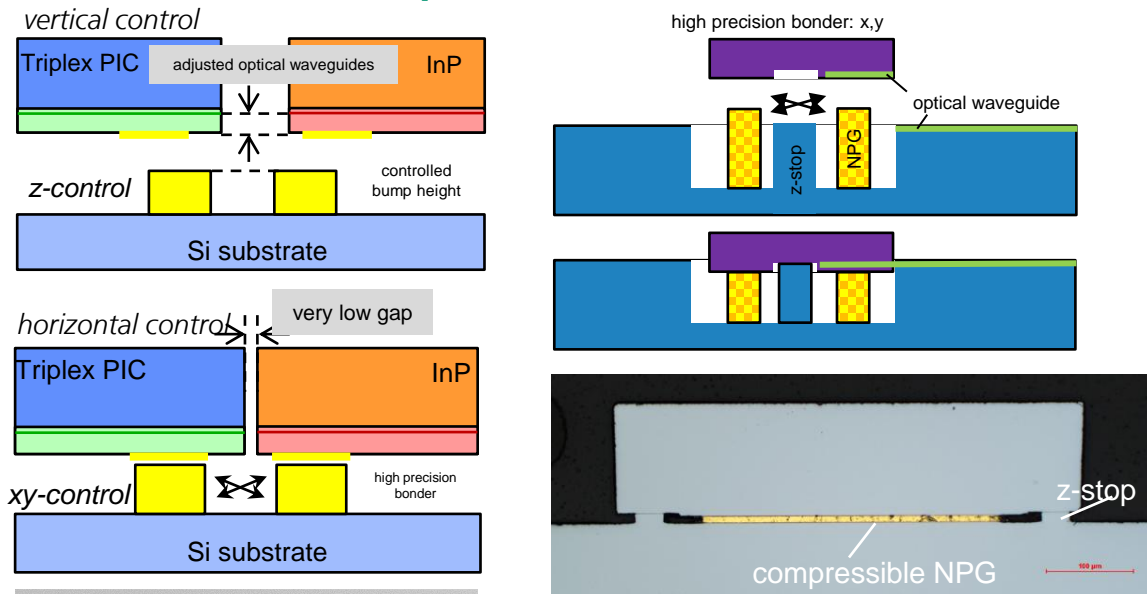
Photonic Component Integration – Optoelectronics to PIC Coupling Schemes



Quantum Packaging: Photonic Layer and Interconnect

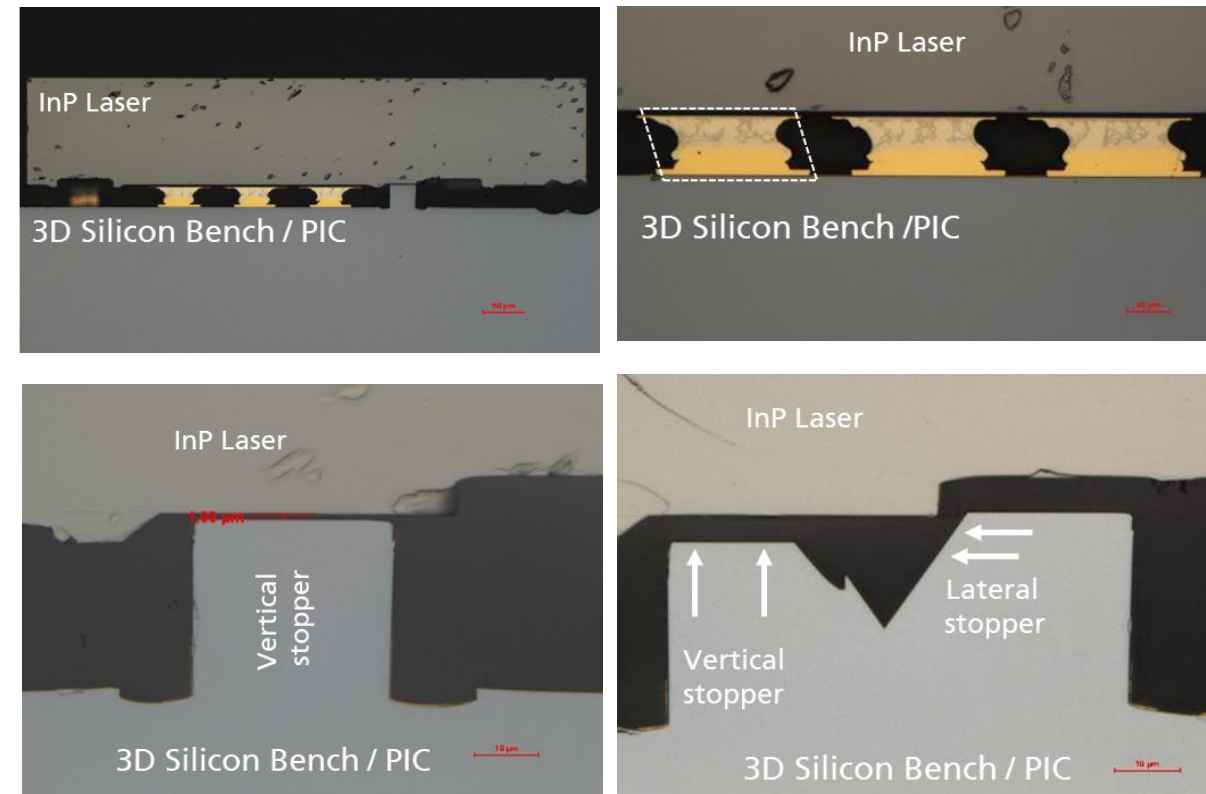
Photonic Component Assembly: Passive Alignment for Optical Chip-to-Chip Coupling

High Precision Bonding using Planarized Au-Au or Nanoporous Gold (NPG)



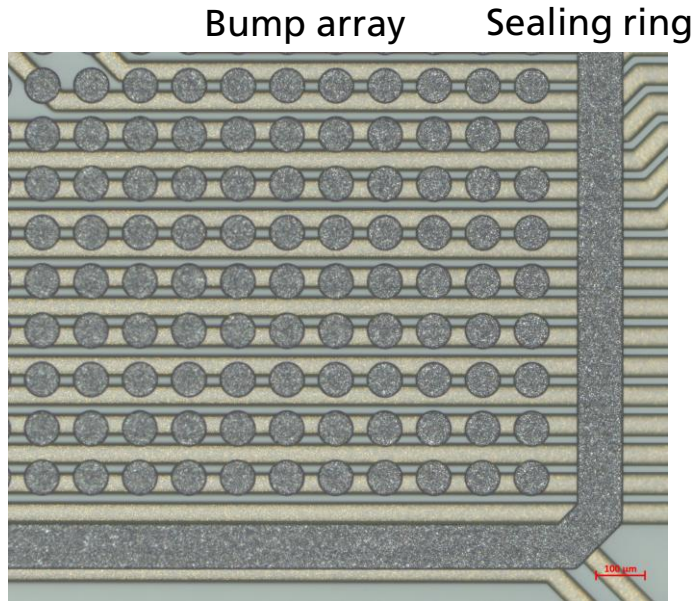
- Compressible Nanoporous gold (NPG)
- low temperature bonding down to 150°C
 - low bonding pressure down to 15 MPa
 - low bonding time (few seconds)
 - tolerant bump planarity
 - topography acceptable

Solder Assisted Self-Alignment with Mechanical Stops using AuSn Solder Bumps

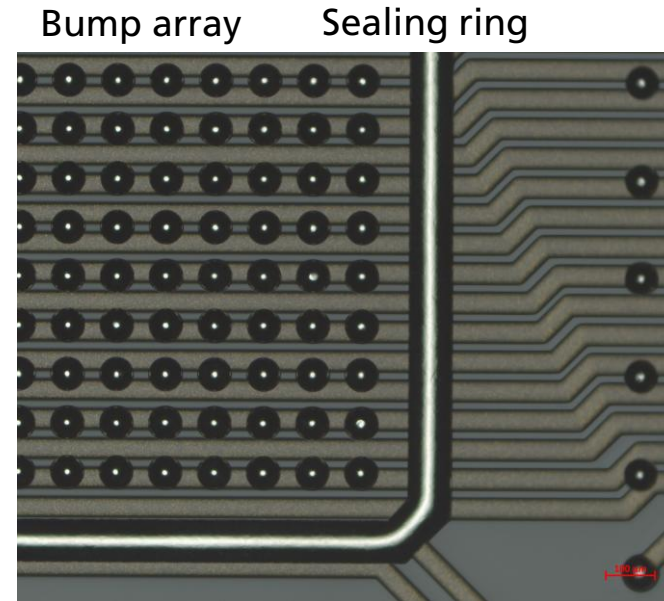


Ion Traps Qubit Packaging

Hermetic Sealing

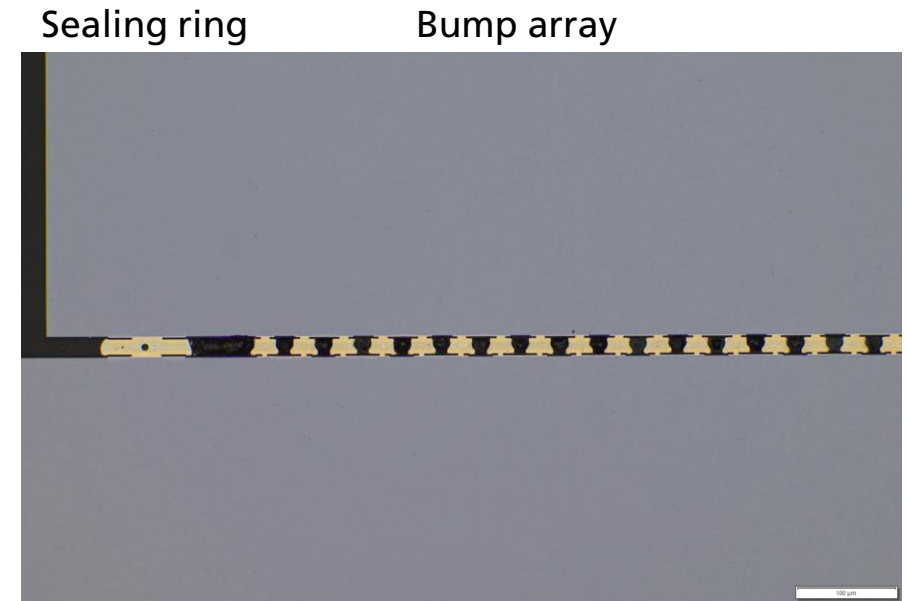


As plated



After reflow

Optional: integration of getter materials



After bonding

- Hermetic sealing at chip or package level to sustain UHV environment
- Encapsulation of outgassing chips or components
- Modular approach with vacuum packages for scaling

Packaging for Advanced Quantum Applications

Integration Technologies of Fraunhofer IZM

Superconducting Interposer

- Redistribution layer (Nb and NbN),
- Superconducting TSVs

Cryo FlipChip

- Bumping indium and indium-tin less than 10 μm pitch
- Fine pitch flip chip bonding

Photonics: PIC Design & Integration Technology

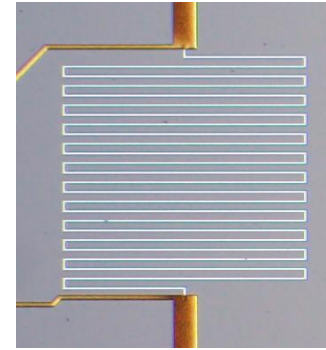
- Chip-to-chip optical coupling solution (butt, GC or evanescent)
- PIC integration technology to connect each qubit
 - Electrical routing on PIC wafer (RF multi-layer, TSVs)
 - Integrate mechanical stops to enhance placement accuracy

Hermetic Sealing

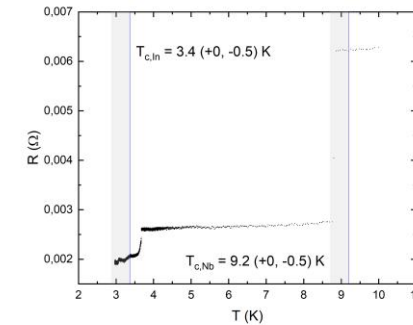
- Vacuum tight hermetic sealing at chip and module level

Cryogenic Test Capabilities

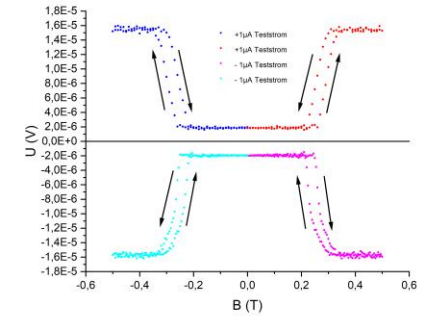
- Temperature ramp from 300K to 3.2 K,
- Magnetic field application up to 0.7 T
- RF capability up to 20 GHz



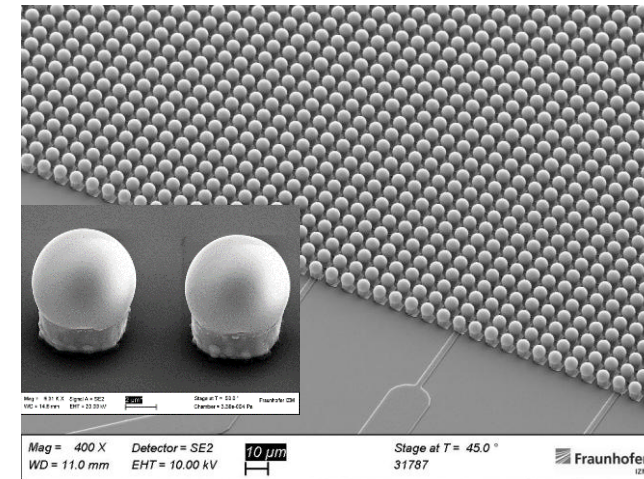
Patterned Nb lines



Test critical temperature



Test critical magnetic field



In bumps
7.5 μm pitch

Kontakt



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Thank you for your attention
